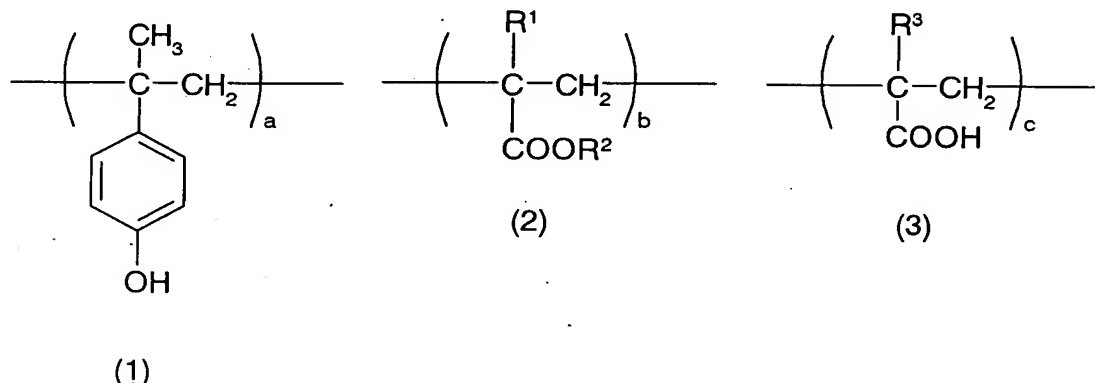


# ABSTRACT OF THE DISCLOSURE

A pattern can be precisely formed by irradiating, with an active energy beam, a positive sensitive resin composition according to this invention comprising a base polymer, an ether-bond-containing olefinic unsaturated compound and an acid-generating agent, where the base polymer is a copolymer comprising the structural units represented by formulas (1) to (3):



where R<sup>1</sup> and R<sup>3</sup> are each independently hydrogen or methyl and R<sup>2</sup> is C<sub>1</sub>-C<sub>6</sub> straight or branched unsubstituted alkyl or C<sub>1</sub>-C<sub>6</sub> straight or branched substituted alkyl, wherein a, b and c are 0.05 to 0.7, 0.15 to 0.8 and 0.01 to 0.5, respectively and a+b+c=1.